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Plasma Sources; 1.0 INTRODUCTION; 2.0 STRUCTURE OF HIGH FREQUENCY CAPACITIVE PLASMAS; 3.0 ENERGY TRANSFER; 4.0 VHF PLASMA PARAMETERS; 5.0 VHF PROCESSING RESULTS; 6.0 SUMMARY; ACKNOWLEDGMENTS; REFERENCES; Chapter 5 Surface Wave Plasma Sources
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5.0 MICROWAVE PLASMA MACHINE PROCESS VARIABLES, AND PERFORMANCE FIGURES OF MERIT6.0 MULTIPOLAR ECR REACTOR PERFORMANCE IN ARGON GAS; 7.0 ECR REACTOR DESIGN CONSIDERATIONS; 8.0 PROCESS APPLICATIONS; 9.0 DISCUSSION; ACKNOWLEDGMENTS; REFERENCES; Chapter 7 Electron Cyclotron Resonance Plasma Sources; 1.0 INTRODUCTION; 2.0 PRINCIPLES OF ECR SOURCE OPERATION; 3.0 SPECIAL ECR CONFIGURATIONS AND APPLICATIONS; 4.0 OPEN ISSUES FOR ECR SOURCES; 5.0 SUMMARY; ACKNOWLEDGMENTS; REFERENCES; Chapter 8 Distributed ECR Plasma Sources; 1.0 INTRODUCTION
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Sommario/riassunto

This book describes the design, physics, and performance of high density plasma sources which have been extensively explored in low pressure plasma processing, such as plasma etching and planarization, plasma enhanced chemical vapor deposition of thin films, sputtered deposition of metals and dielectrics, epitaxial growth of silicon and GaAs, and many other applications. This is a comprehensive survey and a detailed description of most advanced high density plasma sources used in plasma processing. The book is a balanced presentation in that it gives both a theoretical treatment and pr